

Persistent Luminescence (Afterglow) Phosphors

Eu²⁺ activated aluminates					
Host matrix	Emission center	Co-dopant	Emission wavelength [nm]	Afterglow duration	References
MgAl ₂ O ₄	Eu ²⁺	Dy ³⁺	480	>1 min	[1,2]
CaAl ₂ O ₄	Eu ²⁺	Nd ³⁺	440	>5 h	[3-6]
Ca ₁₂ Al ₁₄ O ₃₃	Eu ²⁺	Nd ³⁺	440	>5 min	[7]
SrAl ₁₂ O ₁₉	Eu ²⁺	Dy ³⁺	400	>2 h	[8-10]
SrAl ₄ O ₇	Eu ²⁺	Dy ³⁺	480	>1 h	[8,11-12]
Sr ₄ Al ₁₄ O ₂₅	Eu ²⁺	Dy ³⁺	405, 490	>10 h	[13-16]
SrAl ₂ O ₄	Eu ²⁺	Dy ³⁺	445, 520	>10 h	[17-20]
Sr ₃ Al ₂ O ₆	Eu ²⁺	Dy ³⁺	535,620	>10 min	[8, 21 -24]
BaAl ₂ O ₄	Eu ²⁺	Dy ³⁺	505	>2 h	[25-27]
SrMgAl ₁₀ O ₁₇	Eu ²⁺	Dy ³⁺	460, 515	>3 min	[28]
BaMgAl ₁₀ O ₁₇	Eu ²⁺	Co ³⁺	450	>5 min	[29]
BaCa ₂ Al ₈ O ₁₅	Eu ²⁺	Dy ³⁺	435	>5 min	[30]

Eu²⁺ activated silicates					
Host lattice	Emission center	Co-dopant	Emission wavelength [nm]	Afterglow duration	References
CaMgSi ₂ O ₆	Eu ²⁺	Dy ³⁺ , Nd ³⁺	447	>4 h	[31-33]
Ca ₂ MgSi ₂ O ₇	Eu ²⁺	Tb ³⁺	545	>5 h	[31, 34-36]
Ca ₃ MgSi ₂ O ₈	Eu ²⁺	Dy ³⁺	470	>6 h	[37-38]
CaAl ₂ Si ₂ O ₈	Eu ²⁺	Dy ³⁺ /Pr ³⁺	440	>2 h	[39-41]
Sr ₂ SiO ₄	Eu ²⁺	Dy ³⁺	470, <u>560</u>	>10 min	[42-43]
Sr ₂ MgSi ₂ O ₇	Eu ²⁺	Dy ³⁺	470	>10 h	[44-47]
Sr ₃ MgSi ₂ O ₈	Eu ²⁺	Dy ³⁺	460	>7 h	[38,48]
Sr ₂ Al ₂ SiO ₇	Eu ²⁺	Dy ³⁺	484	>1min	[49]
Sr ₃ Al ₁₀ SiO ₂₀	Eu ²⁺	Ho ³⁺	466	>6 h	[50-51]
Ba ₁₃ Al ₂₂ Si ₁₀ O ₆₆	Eu ²⁺	-	426, 471, 543	>40 min	[52]
Ba ₂ MgSi ₂ O ₇	Eu ²⁺	Tm ³⁺	505	>5 h	[53-54]
Ba ₃ MgSi ₂ O ₈	Eu ²⁺	Dy ³⁺	440	>20 min	[38]
Ba ₄ Si ₆ O ₁₆	Eu ²⁺	Dy ³⁺	506	>24 h	[55]
CaSrAl ₂ SiO ₇	Eu ²⁺	-	444	>20 min	[41]
Ca ₂ ZnSi ₂ O ₇	Eu ²⁺	-	528	>2h	[56]
Sr ₂ ZnSi ₂ O ₇	Eu ²⁺	Dy ³⁺	457	>3 min	[57-58]
Ba ₂ ZnSi ₂ O ₇	Eu ²⁺	Nd ³⁺	505	>1 min	[59]

Other Eu²⁺ activated phosphors					
Host lattice	Emission center	Co-dopant	Emission wavelength [nm]	Afterglow duration	References
Ca ₂ Si ₅ N ₈	Eu ²⁺	Tm ³⁺	610	>1 h	[60-63]
CaAl ₂ B ₂ O ₇	Eu ²⁺	Nd ³⁺	464	>1 h	[64]
SrAl _{1.7} B _{0.3} O ₄	Eu ²⁺	-	520	2	[65]
Ca ₂ P ₂ O ₇	Eu ²⁺	Y ³⁺	415	>6 h	[66]
Sr ₂ P ₂ O ₇	Eu ²⁺	Y ³⁺	420	>8 h	[67]
SrMg ₂ P ₂ O ₈	Eu ²⁺	Ce ³⁺ /Gd ³⁺	400	>2 h	[68]
CaS	Eu ²⁺	Tm ³⁺	650	>1 h	[69-70]
CaGa ₂ S ₄	Eu ²⁺	Ho ³⁺	555	>30 min	[71-72]
Ca ₂ Si ₄	Eu ²⁺	Nd ³⁺	660	>30 min	[73]

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